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"RESPONSE UNDER 37 CFR 1.116-  
EXPEDITED PROCEDURE EXAMINING  
GROUP 1763"

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

TOSHIFUMI NAGAIWA, ET AL.

SERIAL NO: 09/840,178

FILED: APRIL 24, 2001

FOR: WORKTABLE DEVICE AND  
PLASMA PROCESSING  
APPARATUS FOR  
SEMICONDUCTOR PROCESS

: EXAMINER: 1763

: GROUP ART UNIT: KACKAR, R.

RECEIVED  
JAN 10 2003  
TC 1700

AMENDMENT AFTER FINAL

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

This is an amendment responsive to the Office Action dated October 8, 2002, please  
amend the above-identified application as follows:

IN THE CLAIMS

Please cancel claims 2, 7, 15, 16 and 22-24 without prejudice.

Please amend the claims as shown in the marked-up copy to read as follows:

1. (Twice Amended) A worktable device for a semiconductor process, comprising:
- a worktable having a main surface for supporting a target substrate and a sub-surface disposed around said main surface;
  - a cooling mechanism disposed in said worktable and configured to supply cold to the main surface and the sub-surface;
  - a focus ring placed on the sub-surface and configured to surround the target substrate on the main surface, said focus ring consisting essentially of a conductive material;